What is claimed is:

1. $A \ge 4$ kHz repetition rate argon fluoride excimer laser system for producing an UV wavelength 193nm output, said laser system comprising:

18

an argon fluoride excimer laser chamber, said excimer laser chamber for producing a 193nm discharge at a pulse repetition rate \geq 4 kHz, said excimer laser chamber including at least one magnesium fluoride crystal optic window for outputting said 193nm discharge as a \geq 4 kHz repetition rate excimer laser 193nm output, said magnesium fluoride crystal optic window having a 255nm induced absorption less than 0.08 Abs/42mm when exposed to 5 million pulses of 193nm light at a fluence \geq 40mj/cm²/pulse and a 42mm crystal 120nm transmission of at least 30%.

- 2. A laser system as claimed in claim 1 wherein said 42mm crystal 120nm transmission is at least 35%.
- 3. A laser system as claimed in claim 1 wherein said 42mm crystal 120nm transmission is at least 40%.
- 4. A laser system as claimed in claim 1 wherein said magnesium fluoride crystal optic window has a Fe contamination level less than .15ppm Fe by weight.
- 5. A laser system as claimed in claim 1 wherein said magnesium fluoride crystal optic window has a chrome contamination level less than .06ppm chrome by weight.
- 6. A laser system as claimed in claim 1 wherein said magnesium fluoride crystal optic window has a copper contamination level less than .02ppm copper by weight.
- 7. A laser system as claimed in claim 1 wherein said magnesium fluoride crystal optic window has a cobalt contamination level less than .02ppm cobalt by weight.

- 8. A laser system as claimed in claim 1 wherein said magnesium fluoride crystal optic window has an Al contamination level less than .7ppm Al by weight.
- 9. A laser system as claimed in claim 1 wherein said magnesium fluoride crystal optic window has a nickel contamination level less than .02ppm nickel by weight.
- 10. A laser system as claimed in claim 1 wherein said magnesium fluoride crystal optic window has a vanadium contamination level less than .02ppm vanadium by weight.
- 11. A laser system as claimed in claim 1 wherein said magnesium fluoride crystal optic window has a lead contamination level less than .02ppm lead by weight.
- 12. A laser system as claimed in claim 1 wherein said laser system includes a magnesium fluoride crystal optic prism, said magnesium fluoride crystal optic prism external from said excimer laser chamber wherein said ≥ 4 kHz repetition rate excimer laser 193nm output is transmitted through said magnesium fluoride crystal optic prism with said magnesium fluoride crystal optic prism having a 255nm induced absorption less than 0.08 Abs/42mm when exposed to 5 million pulses of 193nm light at a fluence ≥ 40mj/cm²/pulse and a 42mm crystal 120nm transmission of at least 30%.
- 13. A laser system as claimed in claim 1 wherein said magnesium fluoride crystal optic window has an 200 to 210 nm range absorption coefficient < 0.0017 cm⁻¹.
- 14. A laser system as claimed in claim 12 wherein said magnesium fluoride crystal optic prism has an 200 to 210 nm range absorption coefficient < 0.0017 cm⁻¹
- 15. A \geq 4 kHz repetition rate fluoride excimer laser system for producing an UV wavelength λ <200nm output, said laser system comprising:

an excimer laser chamber, said excimer laser chamber for producing an UV wavelength λ <200nm discharge at a pulse repetition rate \geq 4 kHz, said excimer laser chamber including at least one magnesium fluoride crystal optic window for outputting said λ <200nm discharge as a \geq 4 kHz repetition rate excimer laser λ <200nm output, said magnesium fluoride crystal optic window having a 255nm induced absorption less than 00.08 Abs/42mm when exposed to 5 million pulses of 193nm light at a fluence \geq 40mj/cm²/pulse and a 42mm crystal 120nm transmission of at least 30% and a 200 to 210 nm range absorption coefficient < 0.0017 cm⁻¹.

- 16. A laser system as claimed in claim 15 wherein λ is centered about 193nm.
- 17. A laser system as claimed in claim 15 wherein said 42mm crystal 120nm transmission is at least 35%.
- 18. A laser system as claimed in claim 15 wherein said 42mm crystal 120nm transmission is at least 40%.
- 19. A laser system as claimed in claim 15 wherein said magnesium fluoride crystal optic window has a Fe contamination level less than .15ppm Fe by weight.
- 20. A laser system as claimed in claim 15 wherein said magnesium fluoride crystal optic window has a chrome contamination level less than .06ppm chrome by weight.
- 21. A laser system as claimed in claim 15 wherein said magnesium fluoride crystal optic window has a copper contamination level less than .02ppm copper by weight.
- 22. A laser system as claimed in claim 15 wherein said magnesium fluoride crystal optic window has a cobalt contamination level less than .02ppm cobalt by weight.

- 23. A laser system as claimed in claim 15 wherein said magnesium fluoride crystal optic window has an Al contamination level less than .7ppm Al by weight.
- 24. A laser system as claimed in claim 15 wherein said magnesium fluoride crystal optic window has a nickel contamination level less than .02ppm nickel by weight.
- 25. A laser system as claimed in claim 15 wherein said magnesium fluoride crystal optic window has a vanadium contamination level less than .02ppm vanadium by weight.
- 26. A laser system as claimed in claim 15 wherein said magnesium fluoride crystal optic window has a lead contamination level less than .02ppm lead by weight.
- 27. A laser system as claimed in claim 15 wherein said laser system includes a magnesium fluoride crystal optic prism, said magnesium fluoride crystal optic prism external from said excimer laser chamber wherein said \geq 4 kHz repetition rate excimer laser λ <200nm output is transmitted through said magnesium fluoride crystal optic prism with said magnesium fluoride crystal optic prism having a 255nm induced absorption less than 0.08 Abs/42mm when exposed to 5 million pulses of 193nm light at a fluence \geq 40mj/cm²/pulse and a 42mm crystal 120nm transmission of at least 30% .
- 28. A laser system as claimed in claim 15 wherein said magnesium fluoride crystal optic window has a 203 to 207 nm range absorption coefficient < 0.0017 cm⁻¹
- 29. A laser system as claimed in claim 27 wherein said magnesium fluoride crystal optic prism has an 200 to 210 nm range absorption coefficient < 0.0017 cm⁻¹

- 30. A \geq 4 kHz repetition rate fluoride excimer laser crystal optic for transmitting a \geq 4 kHz repetition rate fluoride excimer UV wavelength λ <200nm output, said laser crystal optic comprising a magnesium fluoride crystal with a 255nm induced absorption less than 0.08 Abs/42mm when exposed to 5 million pulses of 193nm light at a fluence \geq 40mj/cm²/pulse and a 42mm crystal 120nm transmission of at least 30% .
- 31. A \geq 4 kHz repetition rate fluoride excimer laser crystal optic as claimed in 30 wherein λ is centered about 193nm.
- 32. A \geq 4 kHz repetition rate fluoride excimer laser crystal optic as claimed in 30 wherein said 42mm crystal 120nm transmission is at least 35%.
- 33. A ≥ 4 kHz repetition rate fluoride excimer laser crystal optic as claimed in 30 wherein said magnesium fluoride crystal has a Fe contamination level less than
 .15ppm Fe by weight.
- 34. A \geq 4 kHz repetition rate fluoride excimer laser crystal optic as claimed in 30 wherein said magnesium fluoride crystal has a chrome contamination level less than .06ppm chrome by weight.
- 35. A \geq 4 kHz repetition rate fluoride excimer laser crystal optic as claimed in 30 wherein said magnesium fluoride crystal has a copper contamination level less than .02ppm copper by weight.
- 36. A \geq 4 kHz repetition rate fluoride excimer laser crystal optic as claimed in 30 wherein said magnesium fluoride crystal has a cobalt contamination level less than .02ppm cobalt by weight.

- 37. A \geq 4 kHz repetition rate fluoride excimer laser crystal optic as claimed in 30 wherein said magnesium fluoride crystal has an Al contamination level less than .7ppm Al by weight.
- 38. A \geq 4 kHz repetition rate fluoride excimer laser crystal optic as claimed in 30 wherein said magnesium fluoride crystal has a nickel contamination level less than .02ppm nickel by weight.
- 39. A \geq 4 kHz repetition rate fluoride excimer laser crystal optic as claimed in 30 wherein said magnesium fluoride crystal has a vanadium contamination level less than .02ppm vanadium by weight.
- 40. A \geq 4 kHz repetition rate fluoride excimer laser crystal optic as claimed in 30 wherein said magnesium fluoride crystal has a lead contamination level less than .02ppm lead by weight.
- 41. A \geq 4 kHz repetition rate fluoride excimer laser crystal optic as claimed in 30 wherein said magnesium fluoride crystal optic has a flat planar face oriented normal to a c axis of said magnesium fluoride crystal.
- 42. A \geq 4 kHz repetition rate fluoride excimer laser crystal optic as claimed in 30 wherein said magnesium fluoride crystal optic has a flat planar face oriented nonnormal to a c axis of said magnesium fluoride crystal.
- 43. A \geq 4 kHz repetition rate fluoride excimer laser crystal optic as claimed in 30 wherein said magnesium fluoride crystal has a c axis grown magnesium fluoride crystallographic orientation.
- 44. A \geq 4 kHz repetition rate fluoride excimer laser crystal optic as claimed in 30 wherein said magnesium fluoride crystal has an 200 to 210 nm range absorption coefficient < 0.0017 cm⁻¹.

- 45. A \geq 4 kHz repetition rate fluoride excimer laser crystal optic window for transmitting a \geq 4 kHz repetition rate fluoride excimer UV wavelength λ <200nm output, said laser crystal optic window comprising a magnesium fluoride crystal with a 255nm induced absorption less than 0.08 Abs/42mm when exposed to 5 million pulses of 193nm light at a fluence \geq 40mj/cm²/pulse and a 42mm crystal 120nm transmission of at least 30% and a 200 to 210 nm range absorption coefficient < 0.0017 cm⁻¹.
- 46. A \geq 4 kHz repetition rate argon fluoride excimer laser crystal optic for transmitting an UV wavelength 193nm argon fluoride excimer laser \geq 4 kHz repetition rate output, said laser crystal optic comprising a magnesium fluoride crystal with a 255nm induced absorption less than 0.08 Abs/42mm when exposed to 5 million pulses of 193nm light at a fluence \geq 40mj/cm²/pulse and a 42mm crystal 120nm transmission of at least 30%.
- 47. A λ <200nm optical fluoride crystal for transmitting a UV wavelength λ <200nm, said λ <200nm optical fluoride crystal comprising a magnesium fluoride crystal with a 255nm induced absorption less than 0.08 Abs/42mm when exposed to 5 million pulses of 193nm light at a fluence \geq 40mj/cm²/pulse and a 42mm crystal 120nm transmission of at least 30% and a Fe contamination level less than 0.17 ppm Fe by weight, a chrome contamination level less than 00.08 ppm chrome by weight, a copper contamination level less than 0.04 ppm copper by weight, a cobalt contamination level less than 0.04 ppm cobalt by weight, an Al contamination level less than 0.9 ppm Al by weight, a nickel contamination level less than 0.04 ppm nickel by weight, a vanadium contamination level less than 0.04 ppm vanadium by weight, and a lead contamination level less than 0.04 ppm lead by weight and a 200 to 210 nm range absorption coefficient < 0.0017 cm⁻¹.
- 48. A λ <200nm optical fluoride crystal as claimed in claim 47, said magnesium fluoride crystal having a Fe contamination level less than 0.15 ppm Fe by weight, a

chrome contamination level less than 0.06 ppm chrome by weight, a copper contamination level less than 0.02 ppm copper by weight, a cobalt contamination level less than 0.02 ppm cobalt by weight, an Al contamination level less than 0.7 ppm Al by weight, a nickel contamination level less than 0.02 ppm nickel by weight, a vanadium contamination level less than 0.02 ppm vanadium by weight, and a lead contamination level less than 0.02 ppm lead by weight.

- 49. A \geq 4 kHz repetition rate argon fluoride excimer laser crystal for transmitting an UV wavelength 193nm argon fluoride excimer laser \geq 4 kHz repetition rate output, said laser crystal comprising a magnesium fluoride crystal with a 255nm induced absorption less than 0.08 Abs/42mm when exposed to 5 million pulses of 193nm light at a fluence \geq 40mj/cm²/pulse and a 42mm crystal 120nm transmission of at least 30% and a Fe contamination level less than 0.17 ppm Fe by weight, a chrome contamination level less than 00.08 ppm chrome by weight, a copper contamination level less than 0.04 ppm copper by weight, a cobalt contamination level less than 0.04 ppm cobalt by weight, an Al contamination level less than 0.9 ppm Al by weight, a nickel contamination level less than 0.04 ppm nickel by weight, a vanadium contamination level less than 0.04 ppm vanadium by weight, and a lead contamination level less than 0.04 ppm lead by weight.
- 50. A ≥ 4 kHz repetition rate argon fluoride excimer laser crystal as claimed in claim 47, said magnesium fluoride crystal having a Fe contamination level less than 0.15 ppm Fe by weight, a chrome contamination level less than 0.06 ppm chrome by weight, a copper contamination level less than 0.02 ppm copper by weight, a cobalt contamination level less than 0.02 ppm cobalt by weight, an AI contamination level less than 0.7 ppm AI by weight, a nickel contamination level less than 0.02 ppm nickel by weight, a vanadium contamination level less than 0.02 ppm vanadium by weight, and a lead contamination level less than 0.02 ppm lead by weight.